

	Hits	Search Text	DBs
1	15	((resist or photoresist) same (first or initial or interference or holograph\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same ((line near12 space) or array or grat\$4)) and ((second or subsequent or sequential\$4 or epper or project\$4 or binary) near16 (expos\$4 or irradiat\$4 or illuminat\$4) near26 (mask or reticle or photomask) near12 ((second or different or another) near16 (pitch or pattern\$3))) and pitch\$4 and (linewidth or LW) and ("k" or rayleigh)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
2	30	((resist or photoresist) same (first or initial or interference or holograph\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same ((line near12 space) or array or grat\$4)) and ((second or subsequent or sequential\$4 or epper or project\$4 or binary) same (expos\$4 or irradiat\$4 or illuminat\$4) same (mask or reticle or photomask) same ((second or different or another) near16 (pitch or pattern\$3))) and pitch\$4 and (linewidth or LW) and ("k" or rayleigh)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
3	23	((resist or photoresist) same (first or initial or interference or holograph\$4) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((second near18 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near9 writ\$4) or maskless or blanket)) and pitch\$4 and (linewidth or LW) and ((imprint\$4 or (electron near3 beam) or e\$3beam or ion\$3beam) near7 (system or module or apparatus or imping\$4)) and ((second or dual) near26 (photoresist or resist or photosensitive) near16 (expos\$4 or mask or photomask))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

4	3	<p>((resist or photoresist) same (first or initial or interference or holograph\$4) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (((additional or different or another or second) near14 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near9 writ\$4) or maskless or blanket) same (break\$3 or non\$4contiguous or continuity or bridg\$4 or connect\$4 or interconnect\$3)) and pitch\$4 and (linewidth or LW) and ((imprint\$4 or (electron near3 beam) or e\$3beam or ion\$3beam) near7 (system or module or apparatus or imping\$4)) and ((second or dual) near26 (photoresist or resist or photosensitive) near16 (expos\$4 or mask or photomask))</p>	<p>US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB</p>
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	Hits	Search Text	DBs
5	19	((resist or photoresist) same (first or initial or interference or holograph\$4) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (((additional or different or another or second) near14 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near9 writ\$4) or maskless or blanket) same (break\$3 or non\$4contiguous or continuity or bridg\$4 or connect\$4 or interconnect\$3)) and pitch\$4 and (linewidth or LW) and ((imprint\$4 or (electron near3 beam) or e\$3beam or ion\$3beam) near7 (system or module or apparatus or imping\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB